

# Tribomechanical properties of DLC coatings deposited by positive ion assisted magnetron sputtering

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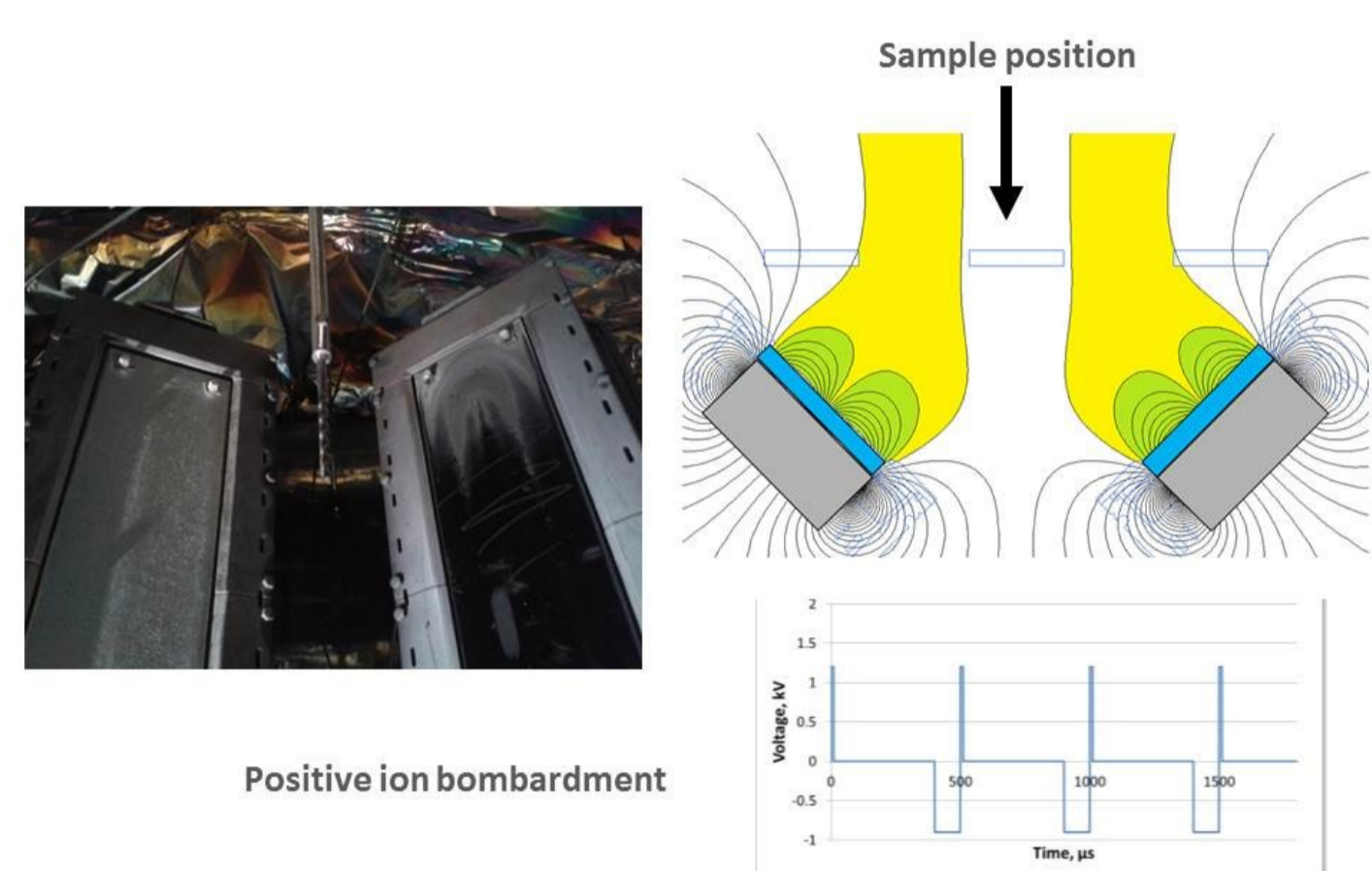
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## Abstract

- Diamond Like Carbon (DLC) presents a very wide spread range of properties.
- DLC coatings can be deposited without sample Bias with high hardness. Thus, DLC coatings can be applied to insulating substrates, such as plastics or glass.
- HIPIMS ion metal etching with Ti and Cr was used successfully to enhance DLC coating adhesion
- Ongoing temperature dependent measurements of the mechanical properties.

## Positive ion assisted magnetron sputtering



Insulating substrates (plastics, glass,...)

Metallic substrates with sharp edges



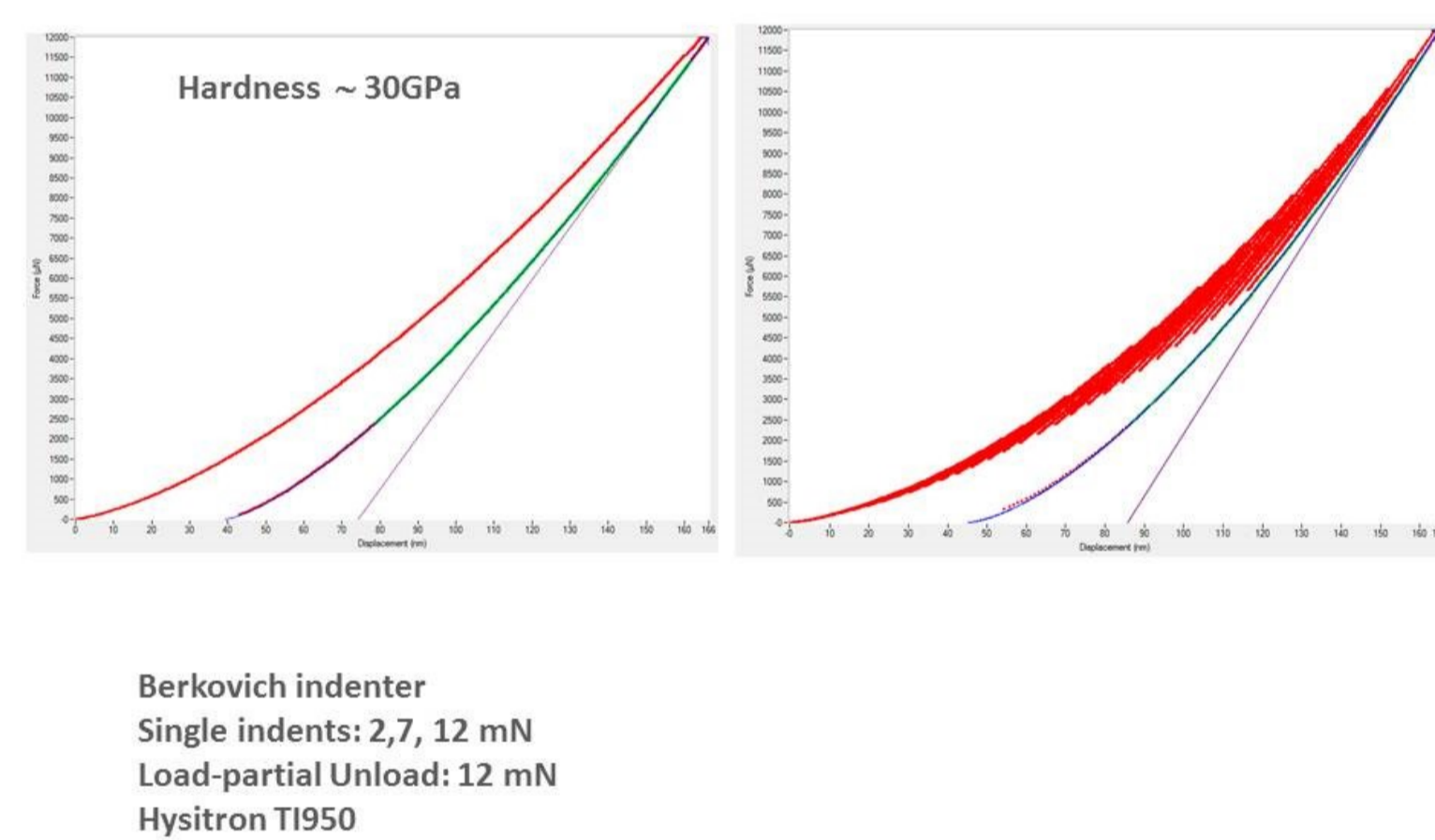
- In magnetron sputtering-DLC deposition ion bombardment plays a key role on the final coating properties
- The authors have found that not only the ion bombardment but also the electron bombardment play key roles on the DLC growth. The use of magnetic and electric field and substrate location arrangements have enabled the authors to control ratio of positive ions and electron bombardment on the substrate.
- High positive Ion Bombardment and low electron bombardment produce hard low stress DLC coatings. High electron plasma interaction produce softer DLC.
- The deposition method has been successfully applied to DLC deposition of a variety of substrates such as tools, glass, plastic surfaces.

Proprietary technology: Patent application number GB1605162.5 (March 2016)

**No samples Bias required!!!**

No flank delamination!

## DLC properties: Nanoindentation



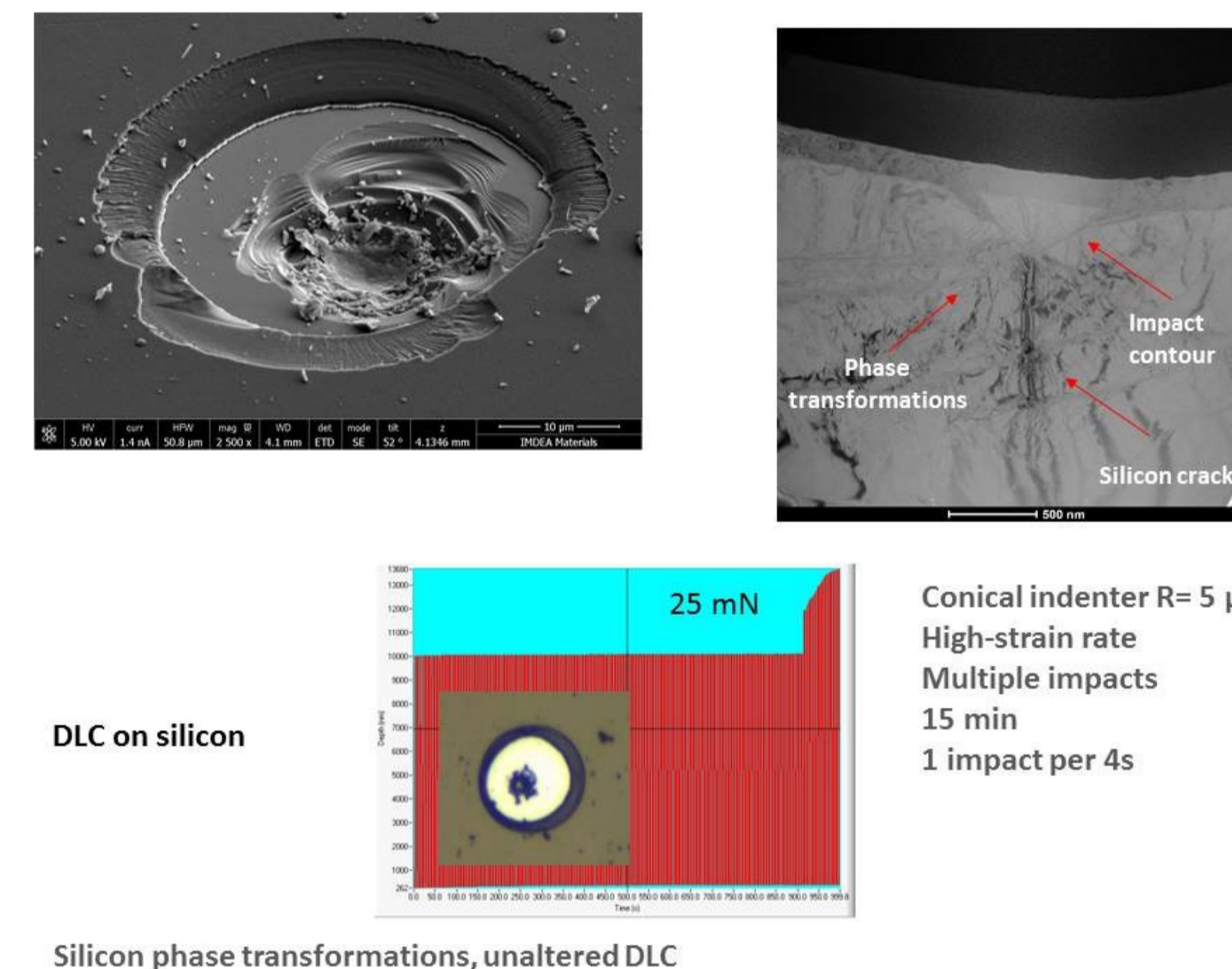
## DLC properties: Friction



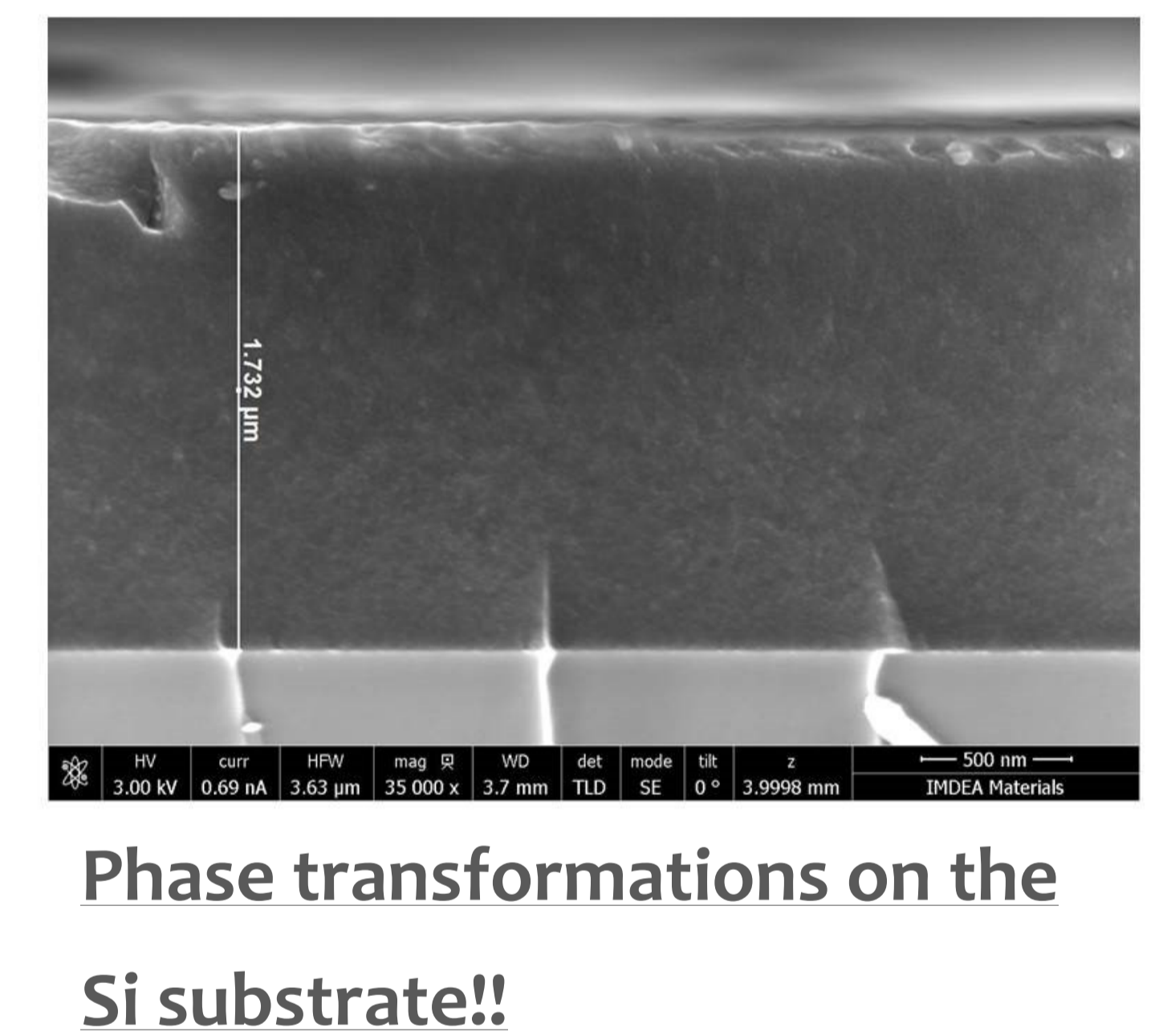
Family	H (GPa)	E (GPa)	$\mu^*$
a-C	30	230	0.18
a-C:H	25	190	0.14
WC-C	25	210	0.25

Dry conditions  
ASTM G99-04

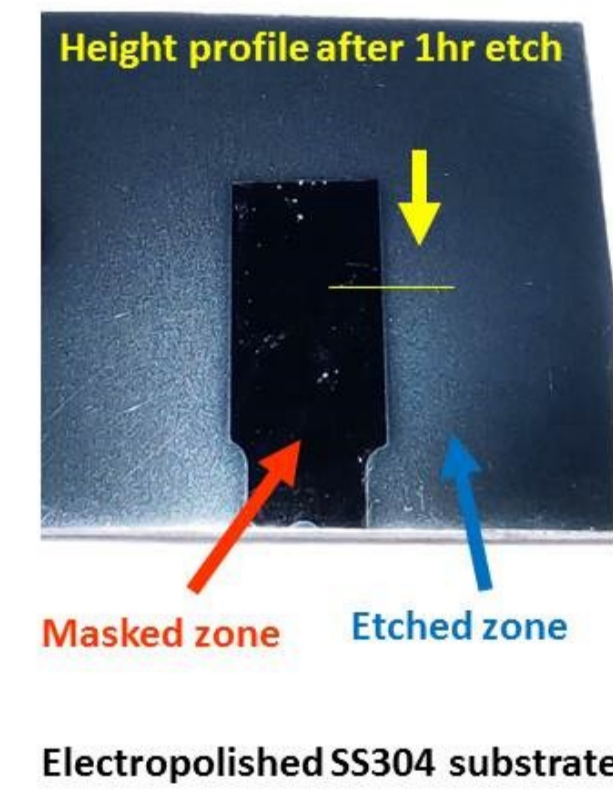
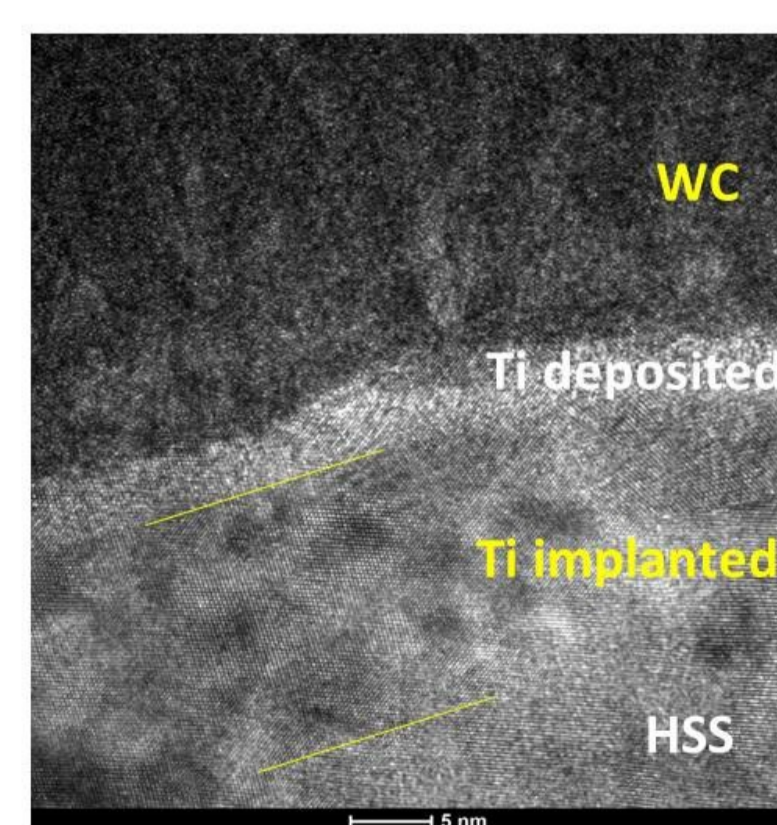
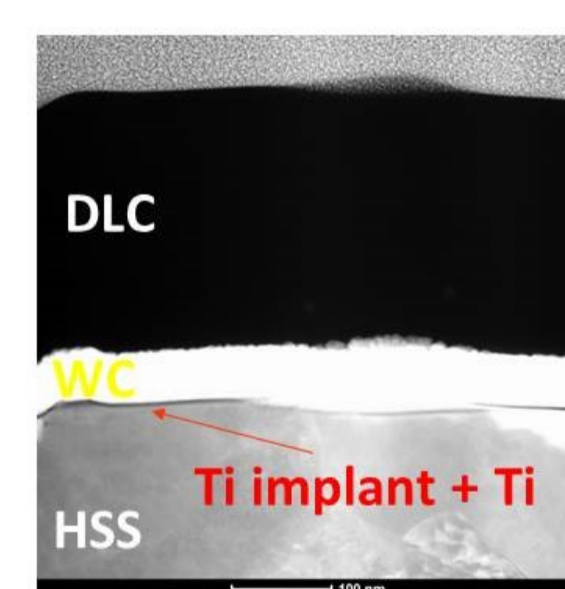
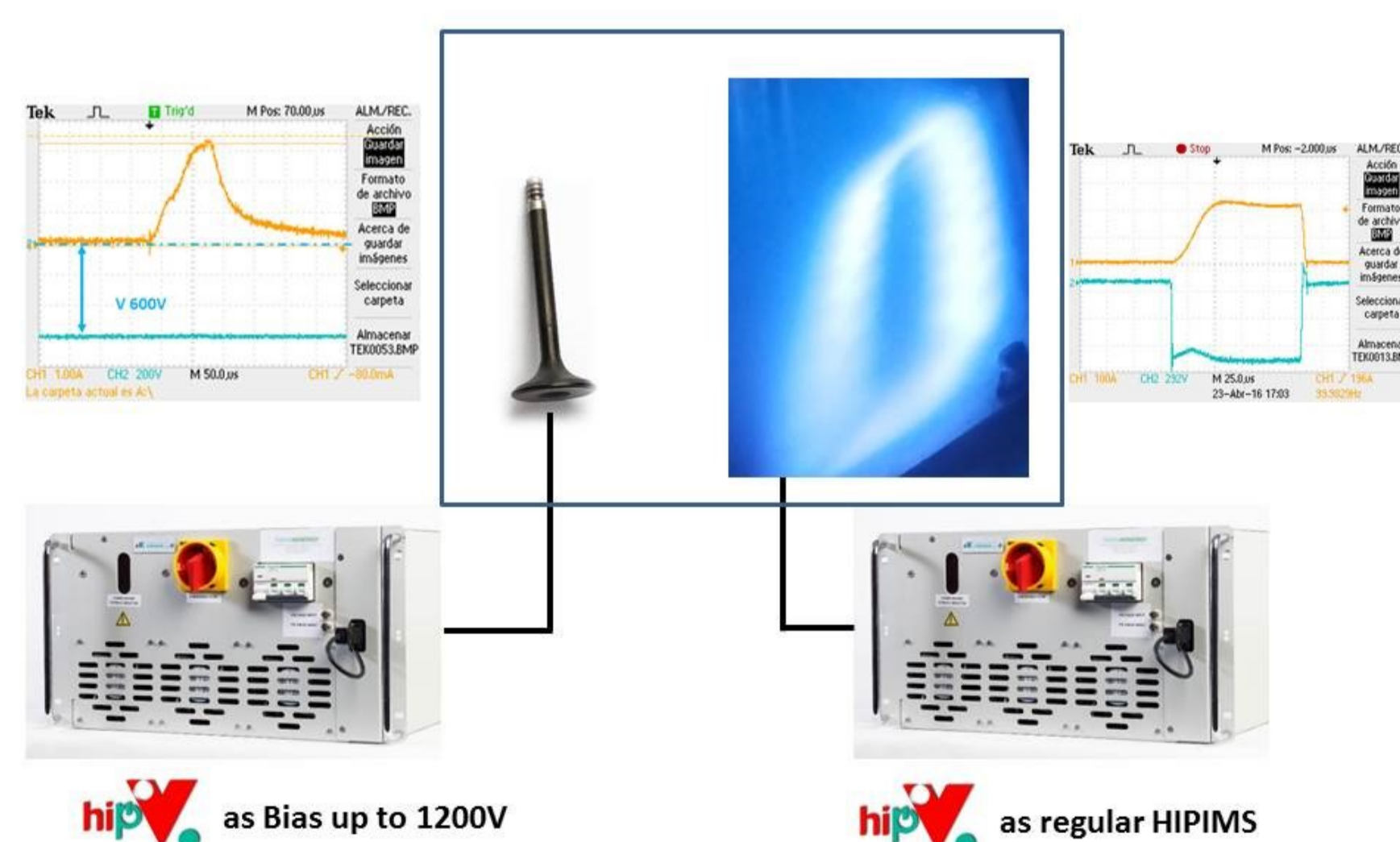
## DLC on silicon: Nano-impact tests



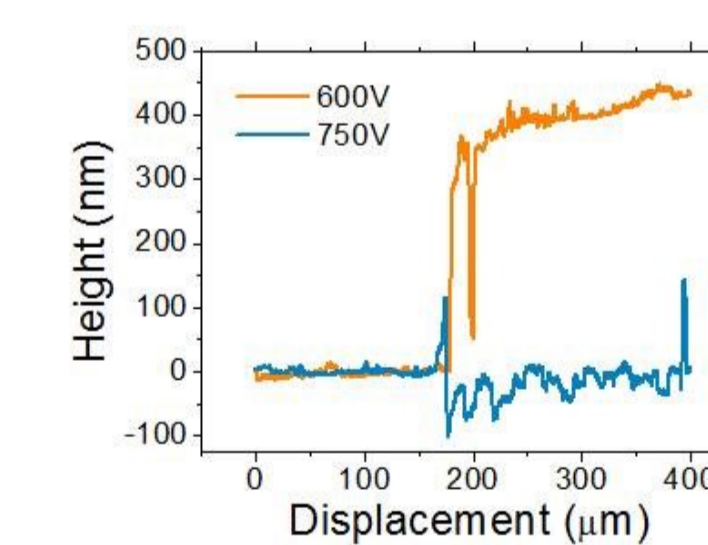
## SEM cross section



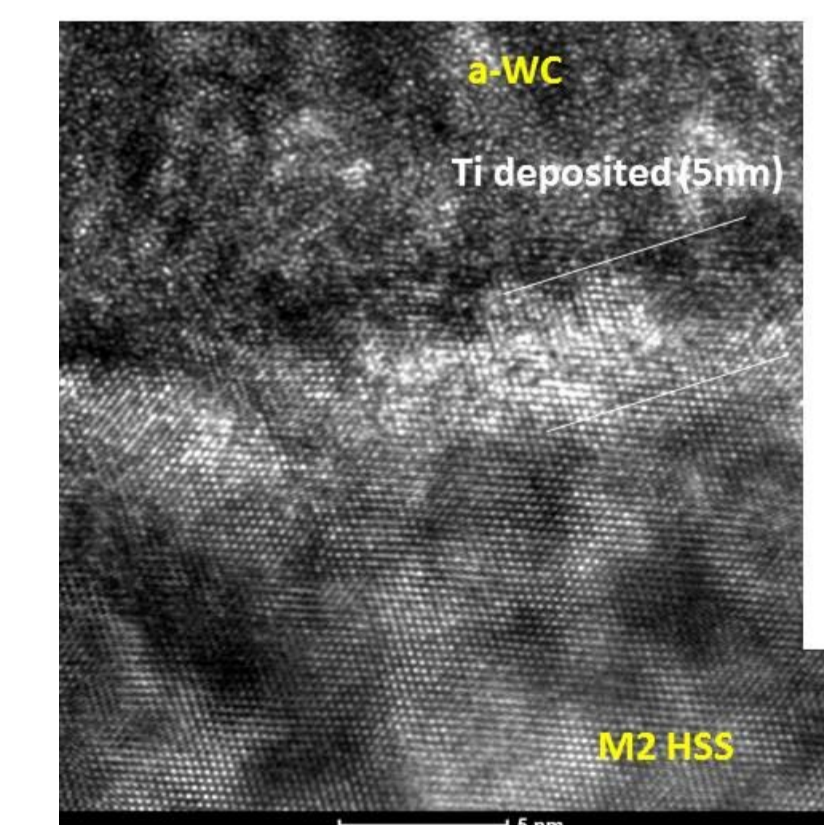
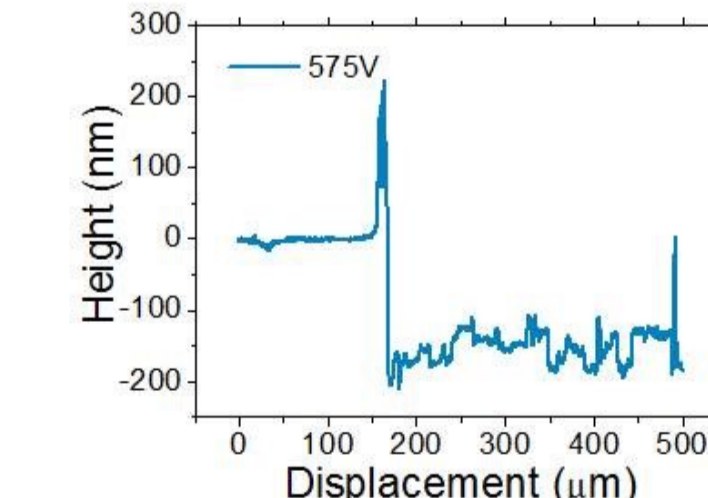
## Adhesion on metal substrates: HiPIMS ion metal etch



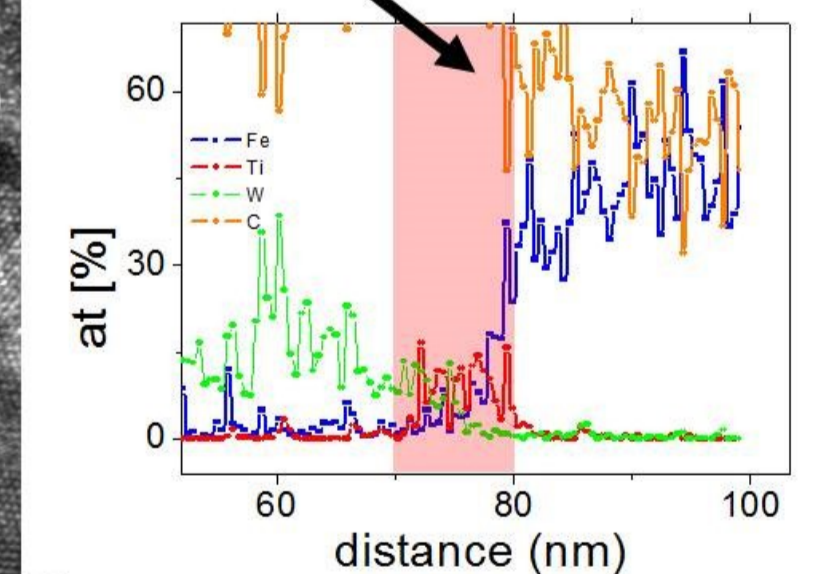
### Cr : Net deposition below 750V Bias



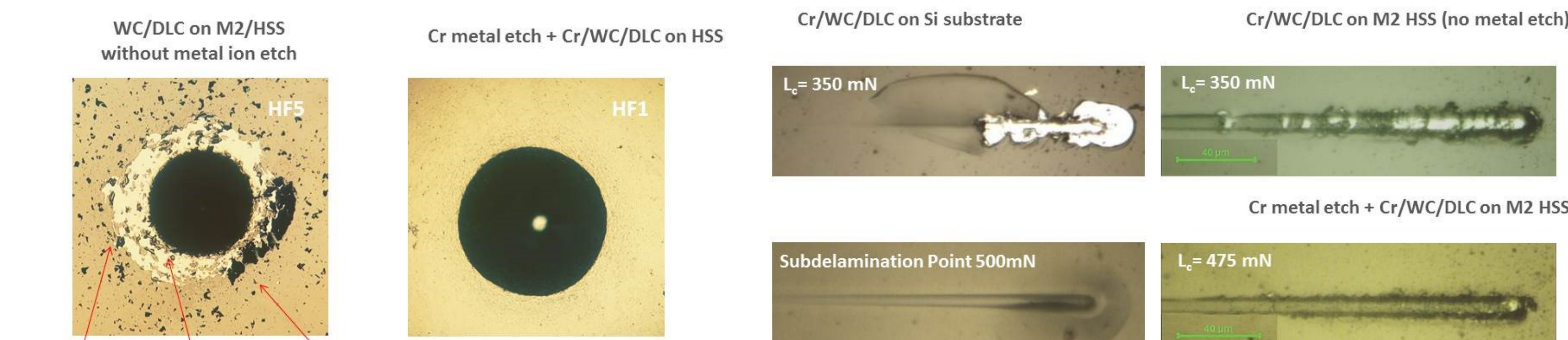
### Ti : Low Bias voltage achievable!



Ti region signal : 10nm (implanted + deposited)



## Adhesion tests: Rockwell, Nano-Scratch



Sphero-conical tip with a tip radius of 10  $\mu$ m  
Scratch length: 500  $\mu$ m  
Maximum normal load: 500 mN  
Loading rate= 2.5 mN/s

Rockwell HRC tests - 150kg - Diamond indenter conical tip

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